

Replacement Specification Sheet

Page 28, lines 13-14

Standard cleaning procedure wafers were processed according to prior art techniques using a process similar to Fig. 1 using the following process parameters. Processing was conducted in a centrifugal spray acid processor produced by Semitool, Inc. of Kalispell MT, Model SAT. The centrifugal spray acid processor can be adapted to including mixing features as explained in U.S. Patent No. 5,954,911, incorporated herein by reference in its entirety to provide explanation of exemplary systems used to mix gaseous phase carriers and vapors generated from liquids. Such application is attached hereto as an Appendix for convenience.